

ABSTRACT

The present invention relates to a device for controlling a gas flow of an equipment front end module (EFEM), which is installed at one side or each of both sides of an internal space of the EFEM to form a gas layer at an entrance, through which a wafer is loaded and unloaded, and a semiconductor process apparatus including the same, and includes a body part installed at an upper portion of a front surface of the entrance, a blower part configured to blow the gas so that the gas is supplied into the body part, a dispersion part installed at a lower portion of the body part. Thus, the present invention may provide an effect of blocking an introduction of external air by installing the body part, the blower part, and the dispersion part at one side or both sides in the internal space of the EFEM to form the gas layer at the entrance of the wafer, thereby forming a blocking gas layer at the entrance so as to reduce humidity of a wafer container.

FIG. 21